

**Amendments to the Claims:**

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) An exposure apparatus comprising:

a projection optical system by which an image of a pattern is projected onto an upper surface of a substrate; and

a stage apparatus, the stage apparatus including:

a holder having a substrate holding surface on which the substrate is held; ~~held, there being a gap along an outer circumferential part of the substrate held on the holder;~~

~~a lyophilic portion a member~~ -that is disposed in a vicinity of the holder radially outward of ~~the~~ ~~an~~ outer circumferential part of the substrate held by the holder, ~~the member including a protruding portion that protrudes radially inward toward and opposes a side surface of the outer circumferential part of the substrate held on the holder such that a gap is provided between the protruding portion and the side surface of the outer circumferential part of the substrate held by the holder, the lyophilic protruding portion being having a downward facing lyophilic surface that faces downward and is disposed lower than the upper surface of the substrate held by the holder; and~~ and facing downward, the downward facing lyophilic portion directly communicating with the gap and extending radially outward from the gap so that a liquid in the gap flows from the gap radially outward to the downward facing lyophilic portion; and

a recovery device that recovers the liquid leaked from the gap using the ~~lyophilic portion surface~~.

2. (Currently Amended) An exposure apparatus according to claim 1, wherein the recovery device has a suction device that suctions the liquid guided to the lyophilic portion surface.

3. (Previously Presented) An exposure apparatus according to claim 2, wherein suction force of the suction device by which the liquid is recovered is greater than suction force by which the substrate is held on the holder.

4. (Currently Amended) An exposure apparatus according to claim 2, wherein the suction device includes a passage disposed below the lyophilic protruding portion, and the lyophilic protruding portion has an inclined portion, which is inclined toward the passage of the suction device, the inclined portion having the downward facing lyophilic surface.

5. (Currently Amended) An exposure apparatus according to claim 1, wherein the downward facing lyophilic portion surface has a first portion that is higher than the substrate holding surface.

6. (Previously Presented) An exposure apparatus according to claim 1, wherein the recovery device has a recessed portion that suctions the liquid by the capillary phenomenon.

7. (Previously Presented) An exposure apparatus according to claim 6, wherein at least a part of the recessed portion is lyophilic.

8. (Currently Amended) An exposure apparatus according to claim 1, wherein the recovery device has member includes a surface that is substantially parallel to the substrate holding surface, and at least a part of which is liquid repellent.

9. (Previously Presented) An exposure apparatus according to claim 1, wherein at least a part of the holder is liquid repellent.

10. (Previously Presented) An exposure apparatus according to claim 1, wherein the substrate holding surface is liquid repellent.

11. (Currently Amended) An exposure apparatus according to claim 1, wherein the lyophilic protruding portion is disposed so that a space is formed between includes a lyophilic radially innermost side surface that opposes the side surface of the outer circumferential part of the substrate and the lyophilic portion held by the holder.

12. (Currently Amended) An exposure apparatus according to claim 1, wherein a portion of the holder that opposes the lyophilic protruding portion is liquid repellent.

13. (Canceled)

14. (Currently Amended) An exposure method comprising:

holding a substrate on a holder, there being a lyophilic portion a member disposed in a vicinity of the holder radially outward of an outer circumferential part of the substrate held by the holder, the member including a protruding portion that protrudes radially inward toward and opposes a side surface of the outer circumferential part of the substrate held on the holder such that a gap is provided between the protruding portion and the side surface of the outer circumferential part of the substrate held by the holder, the protruding portion having a downward facing lyophilic surface that faces downward and is disposed lower than an upper surface of the substrate held by the holder; in a vicinity of the holder radially outward of an outer circumferential part of the substrate held by the holder, the lyophilic portion facing downward;

supplying liquid to the upper surface of the substrate; and

irradiating an image of a pattern onto the upper surface of the substrate held by the holder through the liquid,

wherein the downward facing lyophilic portion directly communicates with a gap that surrounds the substrate held by the holder and extends radially outward from the gap so that the liquid in the gap flows from the gap radially outward to the downward facing lyophilic portion surface.

15. (Currently Amended) An exposure method according to claim 14, further comprising:

recovering part of the liquid using the lyophilic portion surface.

16. (Previously Presented) An exposure method according to claim 14, wherein a part of the holder is liquid repellent.

17. (Currently Amended) An exposure apparatus according to claim 11, wherein the lyophilic portion has an inclined surface which downward facing lyophilic surface is downwardly inclined in a direction away from the substrate held on the holder.

18. (Currently Amended) An exposure apparatus according to claim 1, further comprising wherein:

the protruding portion includes a flat upper surface which is provided around the holder, and which is substantially flush with the upper surface of the substrate held on the holder,

wherein the recovery device recovers, using the lyophilic portion surface, the liquid which has leaked from a gap a space between the flat upper surface and the upper surface of the substrate held on the holder.

19. (Currently Amended) The exposure apparatus according to claim 1, further comprising:

a liquid supply system which has a supply port, the liquid supply system supplying a the liquid onto the substrate to form a liquid immersion area on a portion of a the upper surface of the substrate during the exposure,

wherein the substrate is exposed through the liquid with exposure light.

20. (Currently Amended) A device manufacturing method comprising:

exposing, through a the liquid, a the substrate held on a the holder of a the stage apparatus of an the exposure apparatus according to claim 1; and

processing the exposed substrate.

21. (New) An exposure apparatus according to claim 1, wherein at least a part of the protruding portion having the downward facing lyophilic surface has a thickness that is smaller than a thickness of the substrate.

22. (New) An exposure apparatus according to claim 1, wherein at least a part of the downward facing lyophilic surface is disposed higher than a lower surface of the substrate held on the holder.

23. (New) An exposure method according to claim 14, wherein at least a part of the protruding portion having the downward facing lyophilic surface has a thickness that is smaller than a thickness of the substrate.

24. (New) An exposure method according to claim 14, wherein at least a part of the downward facing lyophilic surface is disposed higher than a lower surface of the substrate held on the holder.